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(54) Title: SOLVENTS FOR PROCESSING SILSESQUIOXANE AND SILOXANE RESINS

(57) Abstract: Methods for removing unwanted siloxane and silsesquioxane dielectric film precursor residues from substrates and spin on coating devices are provided. The methods of the invention use liquid silicones to dissolve the film precursors. Solutions of the film precursors in the silicones do not undergo gelling or increase in molecular weight.